

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 10-274852

(43)Date of publication of application : 13.10.1998

(51)Int.Cl.

G03F 7/039
H01L 21/027

(21)Application number : 10-012406

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(22)Date of filing : 26.01.1998

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(30)Priority

Priority number : 09 15353 Priority date : 29.01.1997 Priority country : JP

(54) CHEMICAL AMPLIFICATION TYPE POSITIVE TYPE RESIST COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To improve adhesiveness to a substrate by incorporating a resin having a residue of optionally alkyl substd. butyrolactone and an acid generating agent.

SOLUTION: This resist compsn. contains a resin usually obtd. by (co) polymerizing a compd. having an ethylenic unsatd. bond and an acid generating agent. It is preferable that the resin does not have an arom. ring but has alicyclic rings. The resin has a residue of optionally alkyl substd. butyrolactone. The alkyl is about 1-4C alkyl such as methyl, ethyl or propyl. The acid generating agent generates an acid when it is degraded by the action of radiation such as light or electron beams on the agent or the resist compsn. contg. the agent. The agent is, e.g. an onium salt compd. or an org. halogen compd.

LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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